

FACSIMILE

THIS MESSAGE IS INTENDED ONLY FOR THE USE OF THE INDIVIDUAL OR ENTITY TO WHICH IT IS ADDRESSED AND MAY CONTAIN INFORMATION THAT IS PRIVILEGED, CONFIDENTIAL AND EXEMPT FROM DISCLOSURE UNDER APPLICABLE LAW. IF THE READER OF THIS MESSAGE IS NOT THE INTENDED RECIPIENT OR THE EMPLOYEE OR AGENT RESPONSIBLE FOR DELIVERING THE MESSAGE TO THE INTENDED RECIPIENT, YOU ARE HEREBY NOTIFIED THAT ANY DISSEMINATION, DISTRIBUTION OR COPYING OF THIS COMMUNICATION IS STRICTLY PROHIBITED. IF YOU HAVE RECEIVED THIS COMMUNICATION IN ERROR, PLEASE NOTIFY US IMMEDIATELY, AND RETURN THE ORIGINAL MESSAGE TO US AT THE ADDRESS LISTED BELOW VIA UNITED STATES MAIL. THANK YOU.

Date: September 18, 2003

TO: Office of Initial Patent Examination's
Filing Receipt Corrections

FACSIMILE NO.: (703) 746-9195

FROM: Thomas G. Eschweiler *TGE*
Eschweiler and Associates, LLC
629 Euclid Avenue, Suite 1210
Cleveland, Ohio 44114

Telephone: (216) 502-0600
Facsimile: (216) 502-0601

Re: Filing Receipt for
U.S. Patent Application No. 10/600,775
THIN MAGNETRON STRUCTURES FOR PLASMA GENERATION IN
ION IMPLANTATION SYSTEMS
Filing Date: June 20, 2003
Inventor: Benveniste et al.
Our Ref.: EATNP145US

Attached is a copy of page 1 of the Filing Receipt for the above-referenced application. The last name of the first inventor is misspelled. The name is circled and the correct spelling is 'Benveniste'.

PAGES TRANSMITTED INCLUDING THIS PAGE 2

EATNP/4505



UNITED STATES PATENT AND TRADEMARK OFFICE

UNITED STATES DEPARTMENT OF COMMERCE
United States Patent and Trademark Office
Address: COMMISSIONER OF PATENTS AND TRADEMARKS
P.O. Box 1450
Alexandria, Virginia 22313-1450
www.uspto.gov

APPL NO.	FILING OR 371 (c) DATE	ART UNIT	FIL FEE REC'D	ATTY. DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/600,775	06/20/2003	2821	1236	02-IMP-059	14	47	3

CONFIRMATION NO. 5945

29393

ESCHWEILER & ASSOCIATES, LLC
NATIONAL CITY BANK BUILDING
629 EUCLID AVE., SUITE 1210
CLEVELAND, OH 44114

FILING RECEIPT



OC000000010873588

Date Mailed: 09/15/2003

Receipt is acknowledged of this regular Patent Application. It will be considered in its order and you will be notified as to the results of the examination. Be sure to provide the U.S. APPLICATION NUMBER, FILING DATE, NAME OF APPLICANT, and TITLE OF INVENTION when inquiring about this application. Fees transmitted by check or draft are subject to collection. Please verify the accuracy of the data presented on this receipt. If an error is noted on this Filing Receipt, please write to the Office of Initial Patent Examination's Filing Receipt Corrections, facsimile number 703-746-9195. Please provide a copy of this Filing Receipt with the changes noted thereon. If you received a "Notice to File Missing Parts" for this application, please submit any corrections to this Filing Receipt with your reply to the Notice. When the USPTO processes the reply to the Notice, the USPTO will generate another Filing Receipt incorporating the requested corrections (if appropriate).

Applicant(s)

Benveniste
Victor M. Benveniste, Gloucester, MA;
William F. DiVergilio, Beverly, MA;
Bo H. Vanderberg, Gloucester, MA;

Domestic Priority data as claimed by applicant

This appln claims benefit of 60/470,926 05/15/2003

Foreign Applications

If Required, Foreign Filing License Granted: 09/12/2003

Projected Publication Date: 11/18/2004

Non-Publication Request: No

Early Publication Request: No

Title

Thin magnetron structures for plasma generation in ion implantation systems

